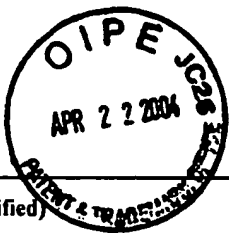


FORM PTO-1449/A and B (Modified) INFORMATION DISCLOSURE STATEMENT BY APPLICANT				APPLICATION NO.: 10/763,819		ATTY. DOCKET NO.: H0498.70130US01	
				FILING DATE: January 23, 2004		CONFIRMATION NO.: Not yet assigned	
				APPLICANT: Tao Deng et al.			
				GROUP ART UNIT: Not yet assigned 1756		EXAMINER: Not yet assigned DUDA	
Sheet	1	of	2				

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				FILING DATE: January 5, 2001 1/23/04	
				APPLICANT: Tao Deng et al.	
				GROUP ART UNIT: Not Yet Assigned 1756	EXAMINER: Not Yet Assigned DUDA
Sheet	2	of	2		

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#EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

*a copy of this reference is not provided as it was previously cited by or submitted to the office in a prior application, Serial No. 09/755,645, filed January 5, 2001, and relied upon for an earlier filing date under 35 U.S.C. 120 (continuation, continuation-in-part, and divisional applications).